



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. 10/636,038
Filing Date August 2, 2003
Inventorship Gurtej S. Sandhu
Assignee Micron Technology, Inc.
Group Art Unit 2824
Examiner Christian D. Wilson
Attorney's Docket No. MI22-2194
Title: Methods of Forming Material on a Substrate, and a Method of Forming a
Field Effect Transistor Gate Oxide on a Substrate

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References - See Attached Form PTO-1449

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. Copies of the cited art are not included (1276 Off. Gaz. Pat. Off 55, 05 August 2003). No admission is made regarding whether all the submitted references are prior art.

This Supplemental Information Disclosure Statement is being filed within three months of the filing date of the application or before the mailing of a first Office Action on the merits, whichever occurs last. Therefore, no fee is believed to be required. However, in the event that a fee is required for filing this Supplemental Information Disclosure Statement, please charge the fee specified under 37 C.F.R. § 1.17(p) to Deposit Account No. 23-0925.

Respectfully submitted,

Dated: 1-12-05

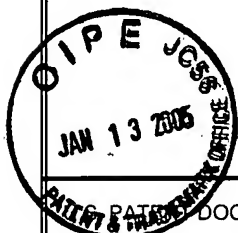
By: 

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Form PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
MI22-2194SERIAL NO.
10/636,038LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)

APPLICANT: Gurtej S. Sandhu

FILING DATE
August 6, 2003GROUP
2824

PATENT DOCUMENTS

*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AJ							
	AK							
	AL							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

	AM		S.M. George, "Atomic layer controlled deposition of SiO ₂ and Al ₂ O ₃ using ABAB...binary reaction sequence chemistry", <i>Elsevier Science B.V., Applied Surface Science 82/83</i> , 1994, p. 460-467.
	AN		
	AO		
EXAMINER	DATE CONSIDERED		

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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